

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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FFICE 2002 | Clade

Application No.: 09/744,877 Filed: January 29, 2001

Inventor(s):

Halimaoui et al.

Title: PROCESS FOR FORMING

AN OXIDE LAYER OF

NON-UNIFORM

THICKNESS ON THE

SURFACE OF A SILICON

SUBSTRATE

Examiner:

Novacek, Christy L.

Group/Art Unit: 2822

Atty. Dkt. No: 5310-03000

CERTIFICATE OF MAILING
UNDER 37 C.F.R. §1.8

DATE OF DEPOSIT:

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first

class mail on the date indicated above and is addressed to:

Commissioner for Patents

Washington, DQ: 20231

Jackie I Pitte

PRELIMINARY AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Amendment

Sir:

Please amend the above-captioned application as follows:

In the Claims:

Please cancel claims 1, 3-7, 9, 11, 12, and 14-17 without prejudice.

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11/25/2002 ACANTY 00